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INFORMATION DISCLOSURE CITATION
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Applicant: Tzeng	
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U.S. PATENT DOCUMENTS

Examiner Initials	Item	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
WM	AA	5,114, 745	05/19/92	Jones	427	113	
WM	AB	4,174,380	11/13/79	Strong, et al.	423	446	
WM	AC	5,202,156	04/13/93	Yamamoto et al.	427	135	
WM	AD	5,270,077	12/14/93	Knemeyer et al.	427	249	
WM	AE	5,364,423	11/15/94	Bigelow et al.	51	293	
WM	AF	5,382,274	01/17/95	Yamamoto et al.	65	26	
WM	AG	5,403,619	040/4/95	Cuomo et al.	427	248	
WM	AH	5,451,430	09/19/95	Anthony et al.	427	372.2	
WM	AI	5,468,326	11/21/95	Cuomo et al.	156	345	
WM	AJ	5,523,121	06/04/96	Anthony et al.	427	249	
WM	AK	5,480,686	01/02/96	Rudder et al	4:27	5:62	

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, etc.)*

WM	AM	High Performance Polishing Techniques for DVD Diamond; Final Report (Phase I) Submitted to Naval Air Warfare Center Under Contract No. N68936-93-C-0246, for period 9/93 – 12/94, Y. Tommy Tzeng – Principal Investigator, Auburn University
WM	AN	Rapid Polishing of Thick Polycrystalline "White" CVD Diamond by Liquid Metal Films, Article, Department of Electrical Engineering, Auburn University, Y. Tzen, J. Wei, c. Cutshaw, and T. Chein
WM	AO	Polishing of CVD Diamond Film, Article Elsevier Science Publishers B.V., 1991, Hitoshi Tokura and Masanori Yoshikawa, Faculty of Engineering, Tokyo Institute of Technology
WM	AP	Microwave CVD of Diamond Using Methanol-Rare Gas Mixtures, M. Buck, T.M. Chuang, J.H. Kaufman and H. Seki; Materials Research Society Symp. Proc. Vol. 162 (1990)
WM	AQ	Applications of Diamond Films and Related Materials, Y. Tzeng, M. Yoshikawa, M. Murakawa and A. Feldman; Materials Sicence Monographs, 73 (1991)
WM	AR	Synthesis of Diamond in High Power-Density Microwave Methane/Hydrogen/Oxygen plasmas at Elevated Substrate Temperatures, T. Chein, J. Wei, and Y. Tzeng, Diamond and Related Materials 8, pp. 1686 - 1696 (1999)
WM	AS	CVD Diamond Grown by Microwave Plasma in Mixtures of Acetone/Oxygen and Acetone/Carbon Dioxide, T. Chein and Y. Tzeng, Diamond and Related Materials 8, pp. 1393 – 1401 (1999)
WM	AT	Toward a General Concept of Diamond Chemical Vapour Deposition, P. Bachmann, D. Leers, and H. Lydtin, Diamond and Related Materials 1, pp. 1 – 12 (1991)

WM	AU	Diamond Synthesis by the Microwave Plasma CVD Method Using a Mixture of Carbon Monoxide and Hydrogen Gas, T. Ito, A. Masuda, Y. Eto, K. Ito, and K. Nishimoto, Science and Technology of New Diamond, pp. 107 – 109 (1990)
WM	AV	Diamond Synthesis from Methane – Hydrogen – Water Mixed Gas Using a Microwave Plasma, Y. Saito, K. Sato, K. Tanaka, K. Fujita and S. Matuda, Hjournal of Materials Science, 23, 842 – 846 (1988)
WM	AW	Effects of Oxygen on CVD Diamond Synthesis, T. Kawato and K. Kondo, Japanese Journal of Applied Physics, pp. 1429 – 1432 (1987)

* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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